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8013-1074

PATENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Hidemitsu AOKI et al.

Confirmation No. 6696

Serial No. 09/715,000

Group 2811

Filed November 20, 2000

IMPROVED SEMICONDUCTOR WAFER SURFACE AND METHOD OF TREATING SEMICONDUCTOR WAFER SURFACE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents

Washington, D.C. 20231

Sir:

In compliance with Rules 1.97 and 1.98, and in full fillment of the duty of disclosure under Rule 1.56, the accordance panying documents, copies of which are attached to this statement, are made of record on the enclosed sheet.

A concise explanation of the relevance of these items is that these references were cited by the Japanese Patent Office in the corresponding Japanese Application Serial No. 11-329324, filed November 19, 1999. A copy of the Japanese Official Action in which they were cited is attached hereto, with what is believed to be the pertinent portion enclosed in a wavy line. An English translation of the enclosed portion is also attached hereto.

Under the provisions of 37 CFR 1.97(e), the undersigned hereby certifies that each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign Patent Office in a

S.N > 09/715,000

counterpart foreign application not more than three months prior to the filing of this Statement.

Respectfully submitted,

YOUNG & THOMPSON

Βv

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January 27, 2003

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

37 CFR 1.98(b)

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

APPLICANT

Hidemitsu AOKI et al.

8013-1074

FILING DATEOD November 20, 2000 GROUP 2811

SERIAL NO.

09/715,000

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

	DOCUMENT NO.	PUBL. DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB GHASS	TRANSLATION YES NO
Al	A 11-40526	02/99	JP		EASS CT	- 70
AJ	A 2000-40679	02/00	JP		101	图 6
AK	A 9-251969	09/97	JP		DGY	三世
AL	A 5-315331	11/93	JP		CEI	VE 2
AM	A 10-72594	03/98	JP		TER	
AN					28	
AO					ي	
AP						
AQ						

OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication)

AT	•	
AU		
AV		
AX		
AY		

EXAMINER

DATE CONSIDERED

EXAMINER: Initial citation considered. Drawline through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form Y&T (3/94)